Noise models for diodes and transistors

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- > pn junctions and BJTs shot noise, flicker noise, burst noise
- MOSFETs flicker noise, thermal noise in strong inversion, shot noise in weak inversion, burst noise
- Shot noise occurs due to various reasons random emission of carriers across a barrier, random tunneling of carriers, generation/recombination processes in bulk and depletion region, thermal fluctuations triggering a relaxation current through diffusion. The PSD of shot noise is proportional to the current
- Some controversy on origin of flicker noise whether it occurs due to number (of carriers) or mobility fluctuations. Models are empirical models.
- Burst noise (or random telegraph signal) is seen as random "bursts" of noise in the time domain - occurs due to charging/discharging of a single defect

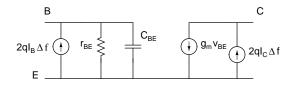
Diodes

- Shot noise occurs because the minority carrier density in the bulk fluctuates due to thermal motion and generation/recombination of carriers. This triggers a relaxation current - the current flow is by diffusion
- The noise spectral density is given as

$$S_I(f) = 2q(I+2I_s)$$

 A more accurate expression includes a frequency dependent term

Bipolar Junction transistor



- Shot noise mechanism is similar to diodes (narrow diodes)
- The spectral densities are given by

$$S_{I_E} = 2qI_E, \quad S_{I_B} = 2qI_B, \quad S_{I_C} = 2qI_C$$

The three noise current sources are correlated

$$S_{CE} = -2qI_C \Rightarrow c_{CE} = -\sqrt{\alpha}$$

 $S_{BE} = -2qI_B \Rightarrow c_{BE} = -\sqrt{\frac{\alpha}{\beta}}$

 The collector base correlation occurs due to charging and discharging of the diffusion capacitance

$$S_{CB} = -2qI_C \frac{j\omega\tau_t}{3} \Rightarrow c_{CB} = -\sqrt{\beta} \frac{j\omega\tau_t}{3}$$

where τ_t is the base transit time

MOSFET - strong inversion

- Random thermal motion of carriers in the inversion layer
- Modelled as a voltage dependent nonlinear resistor
- The noise in the drain current is

$$i_d^2 = 4kTrac{\mu}{L^2}|Q_{inv}|\Delta f$$

where Q_{inv} is the total inversion charge in the MOSFET
▶ In a simple model, ignoring channel length modulation,

$$Q_{inv} = \frac{2}{3} WLC_{ox} (V_{GS} - V_T) \frac{1 + \alpha + \alpha^2}{1 + \alpha}$$

where

$$\alpha = 1 - \frac{V_{DS}}{V_{GS} - V_T}$$

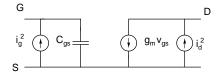
► More complex models take into account velocity saturation

Induced gate noise

- Voltage fluctuations in the channel coupled to the gate through C_g
- Induced gate noise correlated to the drain noise
- A potential fluctuation at v(x) causes a gate current ig given by

$$i_g = -j\omega W \int_o^L C_g(x)v(x)dx$$

Long channel transistor in saturation



For long channel devices in saturation (V_{Dsat} = V_{GS} - V_T), the PSDs of the drain current and induced gate current are

$$S_{i_d} = 4kT \frac{2}{3}g_m, \quad S_{i_g} = 4kT \frac{16}{135} \frac{\omega^2 (WLC_{ox})^2}{g_m}$$

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 The drain and gate noise are correlated and the cross spectral density is

$$S_{i_g i_d *} = 4kT \frac{1}{9} j\omega C_{ox} WL$$

The correlation coefficient (coherence function) is therefore

$$c = \frac{S_{i_g i_d *}}{\sqrt{S_{i_d} S_{i_g}}} \approx 0.395j$$

1/f Noise

- Fluctuations in the curent due to trapping/detrapping by interfacial defects
- A simple model is

$$i_{df}^2 = \frac{Kg_m^2}{WLC_{ox}^2} \frac{1}{f} \Delta f$$

Often just modelled as

$$i_{df}^2 = K' \frac{I_{DS}^a}{f}$$

where a is left as a parameter

K depends on device type and processing

Other noise sources

- Thermal noise due to the distributed gate resistance (R_g)
- ▶ Thermal noise due to source and drain resistances R_s and R_d
- Shot noise due to gate tunneling current and junction diodes

- Noise due to hot electrons (in submicron devices)
- Substrate noise
- RTS noise

References

- 1. A.van der ziel "Noise in solid state devices and circuits"
- 2. A good introduction to noise in MOSFETs is contained in the book "Analysis and modelling of MOS transistors" by Y.Tsividis
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- 4. A.Van der ziel, "Unified presentation of 1/f noise in electronic devices: Fundamental 1/f noise sources", Proc. IEEE, vol.76, no.3, Mar 1988